



POLISHING CLOTH GUIDE



1 SILK

Silk cloth used with alumina or diamond compound on pre-polishing stages on metals or petrographic samples. Recommended use: 9um to 3um diamond and alumina.



2 VEL LAP

White synthetic velvet short nap cloth that provides excellent polish. Used for final polishing on soft metals. Recommended use: 1um and finer diamond, alumina, and colloidal silica. Comparable to Buehler MasterTex and Leco Imperial.



3 RED FELT

100% pure virgin wool fabric plucked rather than sheared pile. Used for general rough and intermediate polishing on all materials. Recommended use: 1um diamond and alumina. Comparable to Struers DP-NAT.



4 FINAL POLISHING CLOTHS

Short, synthetic rayon fibers to woven cotton back giving a soft suede cloth of hard-wearing properties. Good for high removal rates. Recommended use: 1um diamond, alumina, and final polishing on all materials. Comparable to Buehler and Struers Micro and Leco LeCloth.



5 GOLD PADS

Nap free nylon with plastic backing. Provides excellent flatness. Recommended use: 15um to 3um diamond. Comparable to Struers DP-SAT.



6 BLACK CHEM PAD

Porous neoprene. Soft, synthetic, chemically resistant no nap pad that removes smears from tough materials. For final polishing on titanium, stainless teels, lead/tin solders, electronic packages, and soft non-ferrous plastics. Recommended use: 1um and finer diamond, alumina, and colloidal silica. Comparable to Struers DP-CHEM.



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7 NYLON POLISHING CLOTHS

Nylon cloth of close weave, very durable. Recommended use: 15um to 3um diamond to prevent relief and maintain flatness on hard/very hard materials. Comparable to Struers DP-PAN.



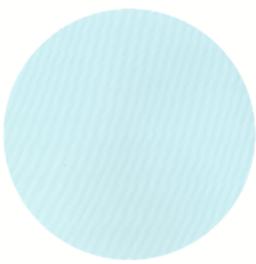
8 TEXPAN POLISHING CLOTH

Low napped for superior edge retention. Commonly used as an intermediate polishing pad for metals and ceramics. Recommended use: 9um, 6um, 3um, 1um diamond with colloidal silica.



9 BURGUNDY CLOTHS

Short napped synthetic burgundy rayon fibers to woven cotton back giving a soft suede cloth of hard-wearing properties. Good for high removal rates. Recommended use: 1um diamond, alumina, and final polishing on all materials. Comparable to Struers DP-NAP



10 ATLANTIS CLOTH

Woven low napped final with a foam backing for better matting to the specimen sample. It is an excellent polishing pad for 1-6 micron diamond. Comparable to Struers DP-DAC.



11 PELLON – PAN W

Synthetic chemotextile hard nap less material which has oil/water resistant backing. Maintaining flatness, edge and inclusion retention in pre-polishing stages on metals and ceramics. Works best with .02-15 micron diamond paste. Equivalent to Buehler Texmet and Leco PAWFA.



12 NYLON HGN WEAVE CLOTH

Polishing cloth for fine grinding of soft metals and pre-polishing of hard materials. Is used for diamond with particle size 15 - 3 µm. Coated, woven polyester. Self-adhesive. Comparable to Struers DP-PLAN